Digitally-aligned ZnO nanowire array based synaptic transistors with intrinsically controlled plasticity for short-term computation and long-term memory

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Figure S1. Schematic diagram of the preparation process of S-ZnO NWs and L-ZnO

NWs.



Figure S2. (a) High-resolution XPS spectra of Zn 2p in ZnO NWs. (b) XRD of S- and L-ZnO NWs. (c) Partial enlargement of XRD of S- and L-ZnO NWs. (d) High-resolution TEM image of S-ZnO NWs. (e) Elemental mapping of ZnO NWs for O. SEM images of diameter of (f) S-ZnO NWs and (g) L-ZnO NWs. (h) OM of ZnO NWs array.



Figure S3. Contrast of SVDP between S-ZnO NWs and L-ZnO NWs.



Figure S4. Contrast of PPF of different voltage between S-ZnO NWs and L-ZnO NWs.



Figure S5. The retention curve of synaptic weight of S-ZnO NWs and L-ZnO NWs with different numbers: (a) 30, (b) 80 and (c) 150.



Figure S6. (a) The LTP of ZnO-NW STs of 300 nm. (b) Postsynaptic responses of S-ZnO-NW STs, ZnO-NW STs of 300 nm and L-ZnO-NW STs after 150 presynaptic inputs (3 V).



Figure S7. Contrast of LTP between (a) S-ZnO NWs and (b) L-ZnO NWs with 150 gate pulses under different voltages (2 V, 2.5 V, 3 V, 3.5 V and 4 V).